

MACROMOLECULAR MATERIAL ABSORBING SHORT-WAVE LIGHT

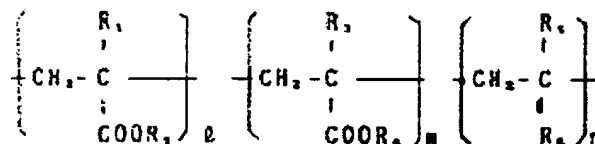
Patent number: JP1207310
Publication date: 1989-08-21
Inventor: SHIMOMURA TAKESHI; others: 02
Applicant: TERUMO CORP
Classification:
- international: C08F220/12; C08F212/00; C08F220/12; C08F220/22;
G03C1/71; G03C1/72; G03C5/16
- european:
Application number: JP19870261045 19871016
Priority number(s):

Report a data error here

Abstract of JP1207310

PURPOSE: To obtain the title material absorbing excimer laser beam capable of etching with a short time exposure and having resistances to etching, consisting of methacrylate, fluoromonomer and a specific aromatic monomer.

CONSTITUTION: The aimed material expressed by the formula (R₁, R₃ and R₅ are H, methyl and ethyl, respectively; R₂ is 1-5C alkyl; R₄ is fluoroalkyl at least one H is substituted with F within 1-8C alkyl) R₆ is a group containing aromatic chain such as naphthalene ring, anthracene ring; l, m and n >=1, respectively and 30 <= (l+m)/n <= 200). The material is preferably obtained by copolymerization with plasma polymerization method of the three; methacrylate such as methyl methacrylate, fluoro-monomer such as trifluoroethyl acrylate and a monomer such as vinyl naphthalene which has a group containing aromatic chain, simultaneously.



Data supplied from the esp@cenet database - Patent Abstracts of Japan